## In the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application.

1. (Original) A method of ellipsometrically measuring a test area on a substrate, the method comprising:

orienting said substrate with respect to an ellipsometer so that an elliptical light spot produced by said ellipsometer fits diagonally within said test area; and measuring the surface properties of said test area with said ellipsometer.

- 2. (Original) The method of Claim 1, further comprising determining an angle of diagonal of said test area.
- 3. (Original) The method of Claim 2, wherein said orienting comprises rotating said substrate by a predetermined angle, so that a major axis of said elliptical light spot is approximately aligned with said angle of diagonal of said test area.
- 4. (Original) The method of Claim 2, wherein said orienting comprises rotating said ellipsometer by a predetermined angle, so that a major axis of said elliptical light spot is approximately aligned with said angle of diagonal of said test area.
- 5. (Original) A method of measuring a test area on a substrate using an elliptical light spot produced by an ellipsometer, the method comprising:

loading a substrate onto a stage;

orienting said substrate with respect to said ellipsometer so that said elliptical light spot fits diagonally within said test area;

producing a light beam with an ellipsometer, said light beam creating said elliptical light spot on said substrate when reflected off of said substrate; and measuring the surface properties of said test area with said ellipsometer.

6. (Original) The method of Claim 5, wherein said elliptical light spot comprises a major axis and a minor axis, said major axis of said elliptical light spot being approximately aligned with a diagonal of said test area.

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- 7. (Original) The method of Claim 5, wherein said sample is loaded onto said stage with the desired orientation.
- 8. (Original) The method of Claim 5, wherein said orienting comprises rotating said substrate by a predetermined angle.
- 9. (Original) The method of Claim 5, wherein said orienting comprises rotating said ellipsometer by a predetermined angle.
- 10. (Original) The method of Claim 5, further comprising calculating an angle of diagonal for said test area, and orienting said substrate with respect to said ellipsometer by said angle of diagonal.
- 11. (Original) A method of measuring a test area on a substrate using an elliptical light spot produced by an ellipsometer, wherein said elliptical light spot has a major axis and a minor axis, the method comprising:

loading a substrate onto a stage;

orienting said substrate with respect to said ellipsometer, so that said major axis of said elliptical light spot is approximately aligned with a diagonal of said test area; producing a light beam with an ellipsometer, said light beam creating said elliptical light spot on said substrate when reflected off of said substrate; and measuring the surface properties of said test area with said ellipsometer.

- 12. (Original) The method of Claim 11, wherein said orienting comprises rotating said substrate by a predetermined angle.
- 13. (Original) The method of Claim 11, wherein said orienting comprises rotating said ellipsometer by a predetermined angle.
- 14. (Original) The method of Claim 11, further comprising calculating an angle of said diagonal, and orienting said substrate with respect to said ellipsometer by said angle of said diagonal.

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